

FORMATION OF ORGANIC MONOMOLECULAR FILM AND METHOD FOR PATTERNING THE SAME

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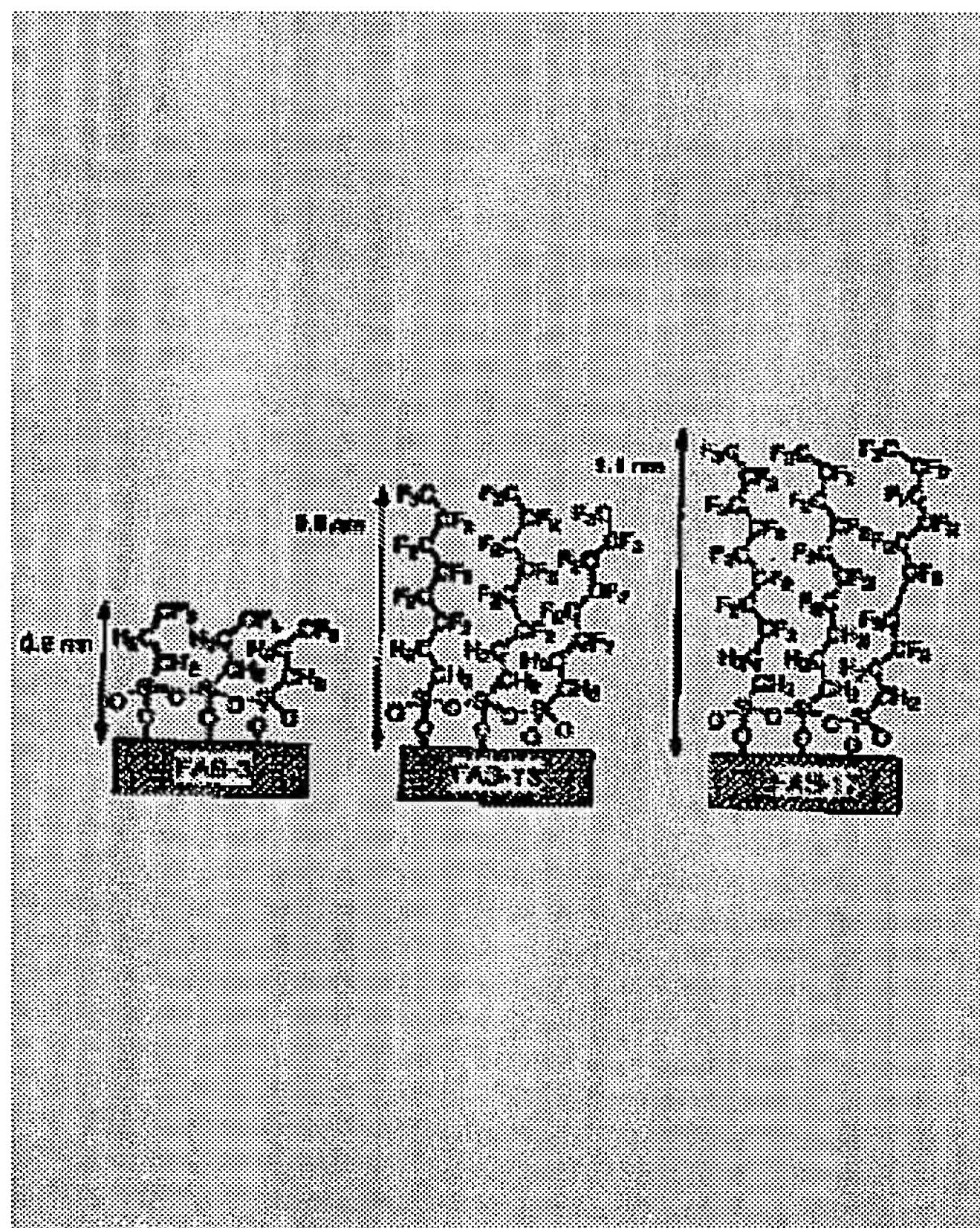
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Abstract of JP2000282240

PROBLEM TO BE SOLVED: To provide a method for self-depositing a dense monomolecular film on a substrate by a simple method and to provide a method for patterning the organic monomolecular film with high precision by a simple method. **SOLUTION:** A substrate is previously cleaned by any method, and thereafter, its surface is made into the hydrophilic one to form a monomolecular film of an alkylsilane fluoride on the substrate by a chemical vapor deposition method, by which the organic monomolecular film is formed. Moreover, by irradiating with ultraviolet rays in an atmosphere contg. oxygen and removing the monomolecular film of the alkylsilane fluoride, the organic monomolecular film is patterned.



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